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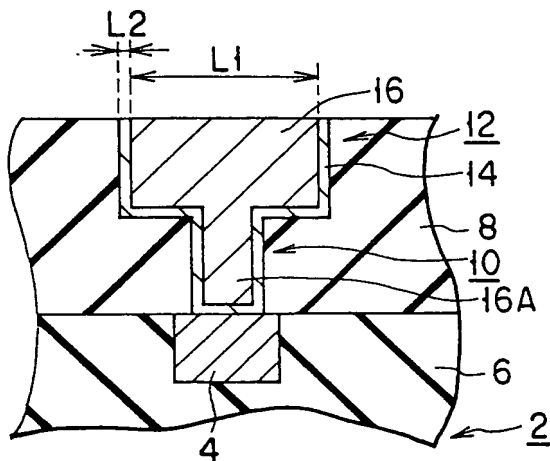


FIG. 1

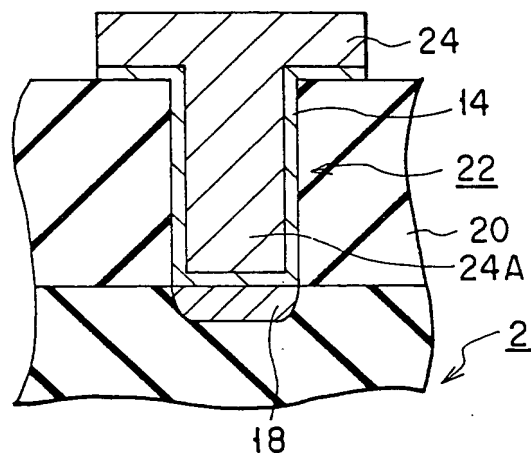


FIG. 2

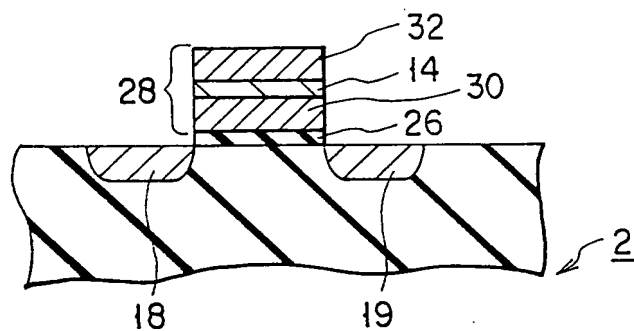


FIG. 3

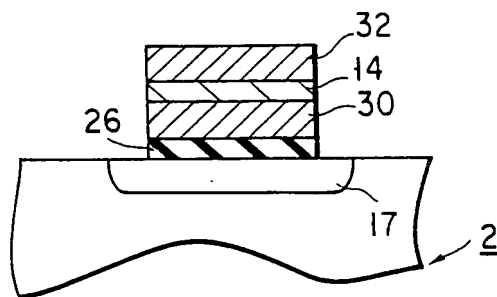
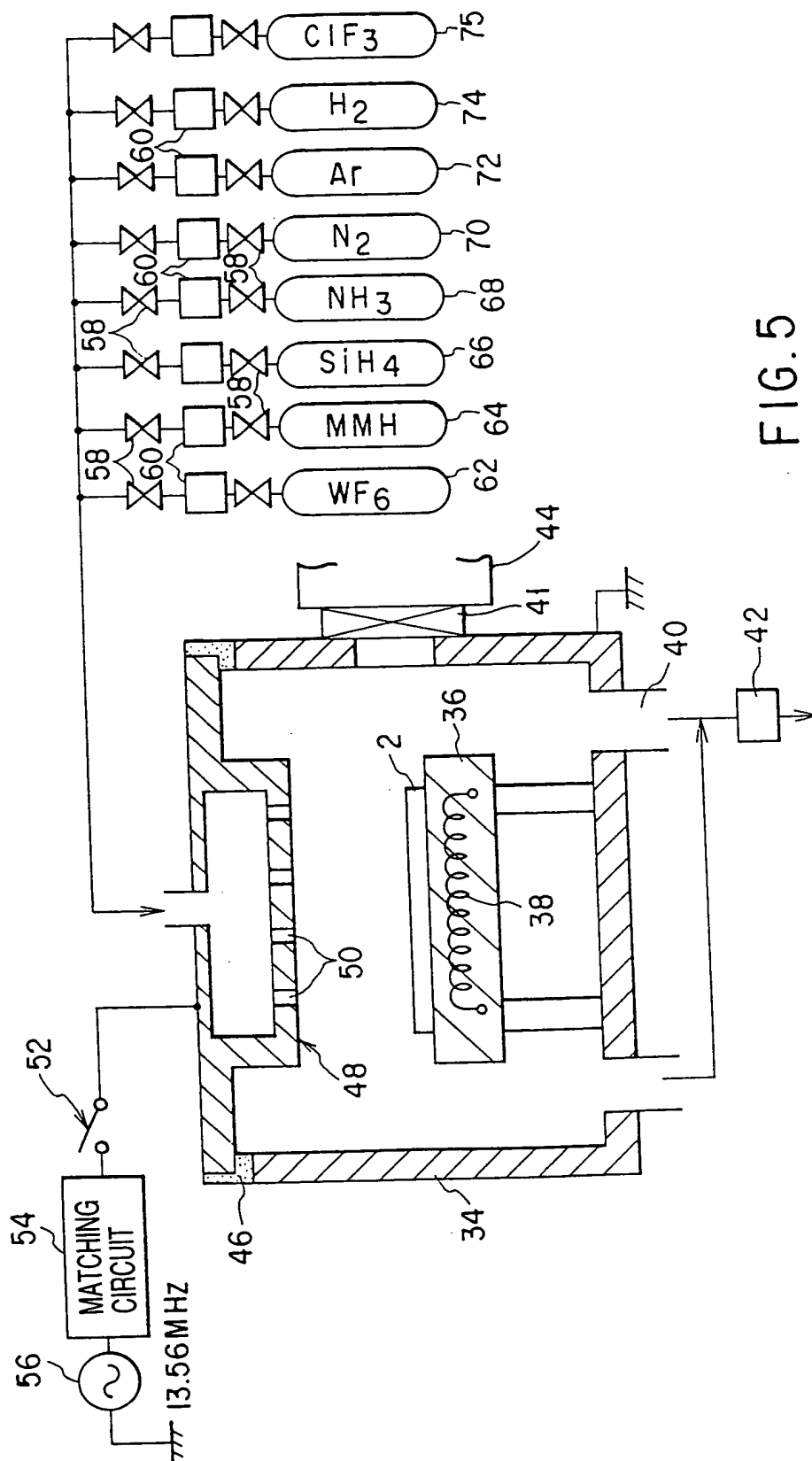


FIG. 4

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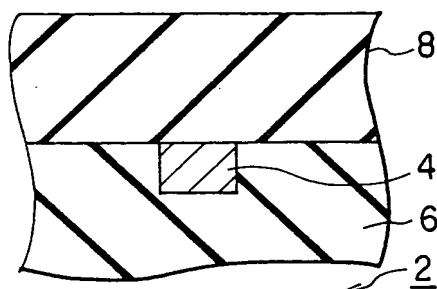


FIG. 6A

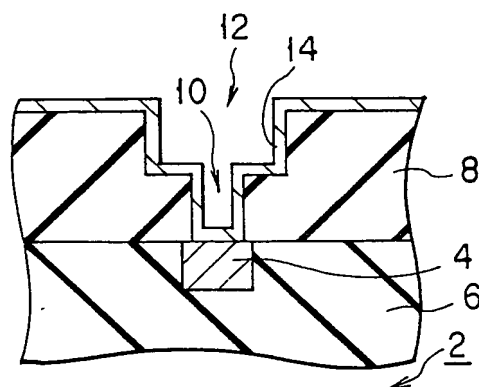


FIG. 6D

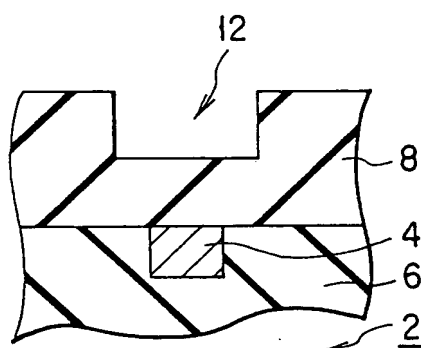


FIG. 6B

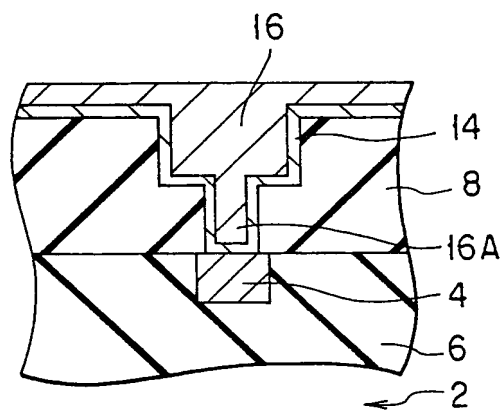


FIG. 6E

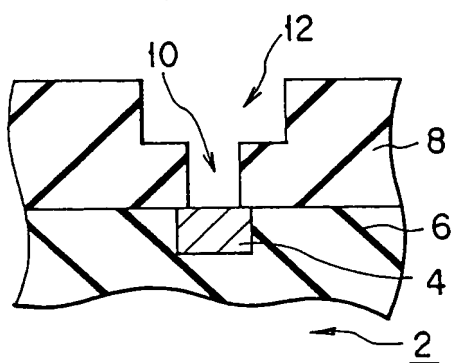


FIG. 6C

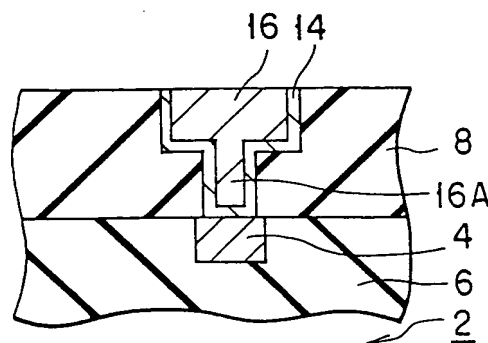


FIG. 6F

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FIG. 7

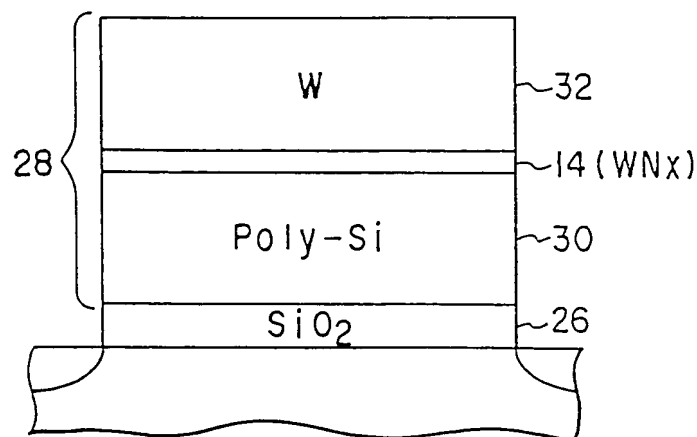
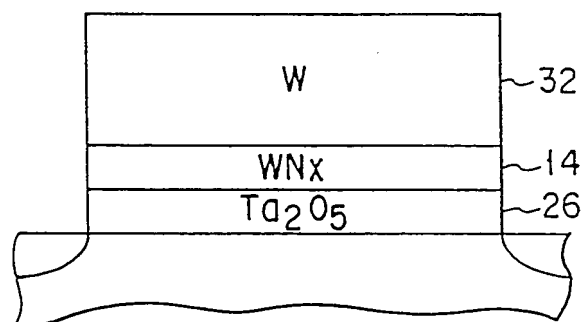


FIG. 8



	COMPARATIVE EXAMPLE 1	COMPARATIVE EXAMPLE 2	PRESENT INVENTION
STRUCTURE	Poly / WSi	Poly / TiSi	Poly / WN / W
RESISTANCE VALUE (uohmcm)	50 -60	20 -30	10
HEAT RESISTANCE (°C)	1000	800	900
CHEMICAL RESISTANCE (HF)	GOOD	POOR	GOOD
ETCHING AMOUNT DURING FILM FORMATION	LARGE	SMALL	SMALL

FIG. 9

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